

Meeting (EMI) requirements with CoolMOS™

Leo Liang
Jan 2018



After attending the training, you will be able to

- Replace standard MOSFET with CoolMOS™ and successfully meet EMI
- Replace previous CoolMOS™ Generations and competitor Super Junction MOSFETs with CoolMOS™ P7 / CE MOSFETs and successfully meet EMI
- Make new designs with CoolMOS™ P7 / CE based power supplies and successfully meet EMI

1

Introduction

2

Methods to improve CoolMOS™ EMI behaviour

- External R_g
- External C_{gd}
- External C_{ds}
- Ferrite beads
- Transformers

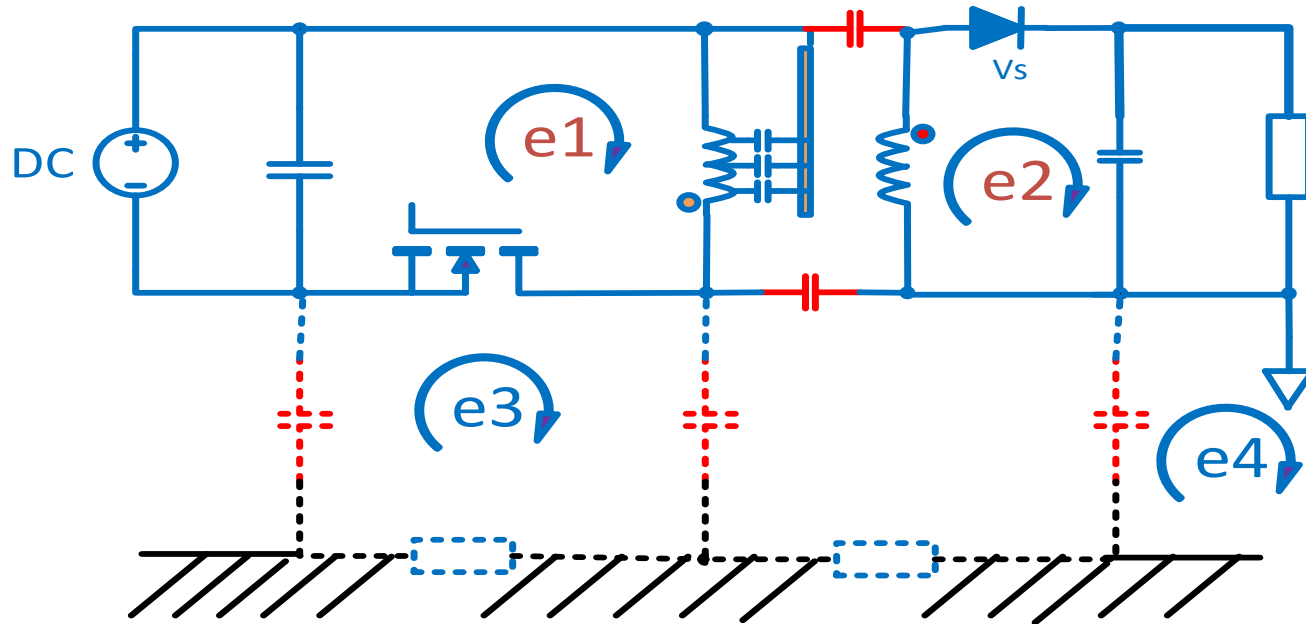
1

Introduction

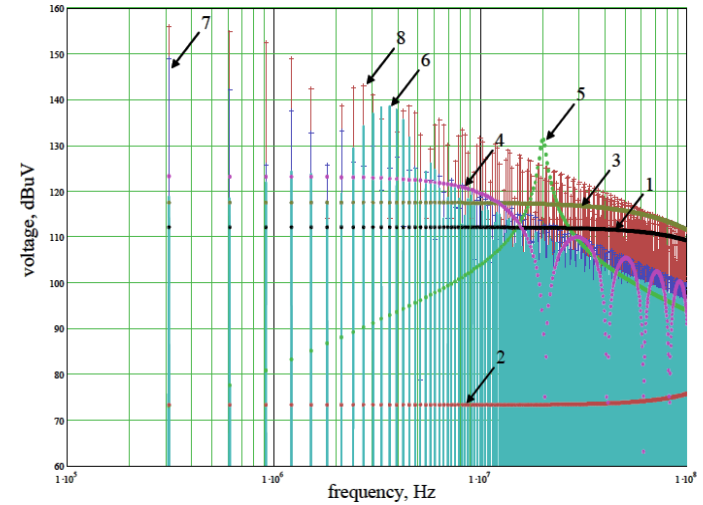
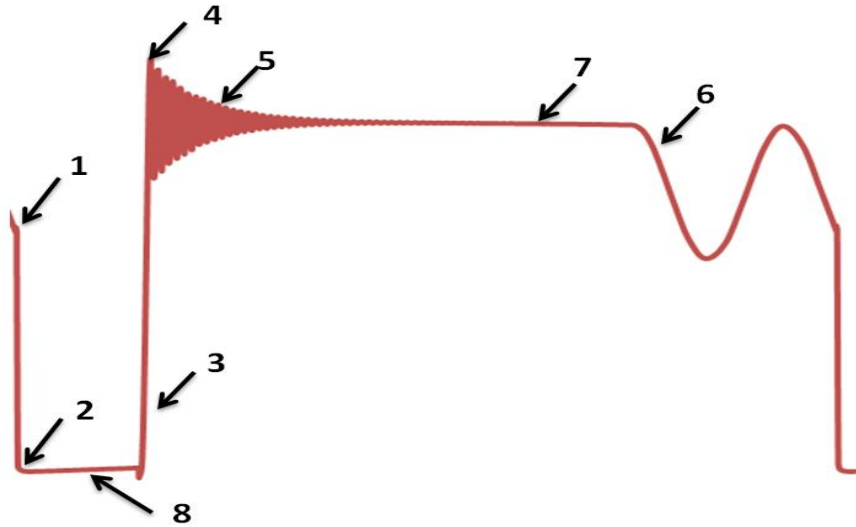
2

Methods to improve CoolMOS™ EMI behaviour

- External R_g
- External C_{gd}
- External C_{ds}
- Ferrite beads
- Transformers



Waveform products frequency spectrum



1

Introduction

2

Methods to improve CoolMOS™ EMI behaviour

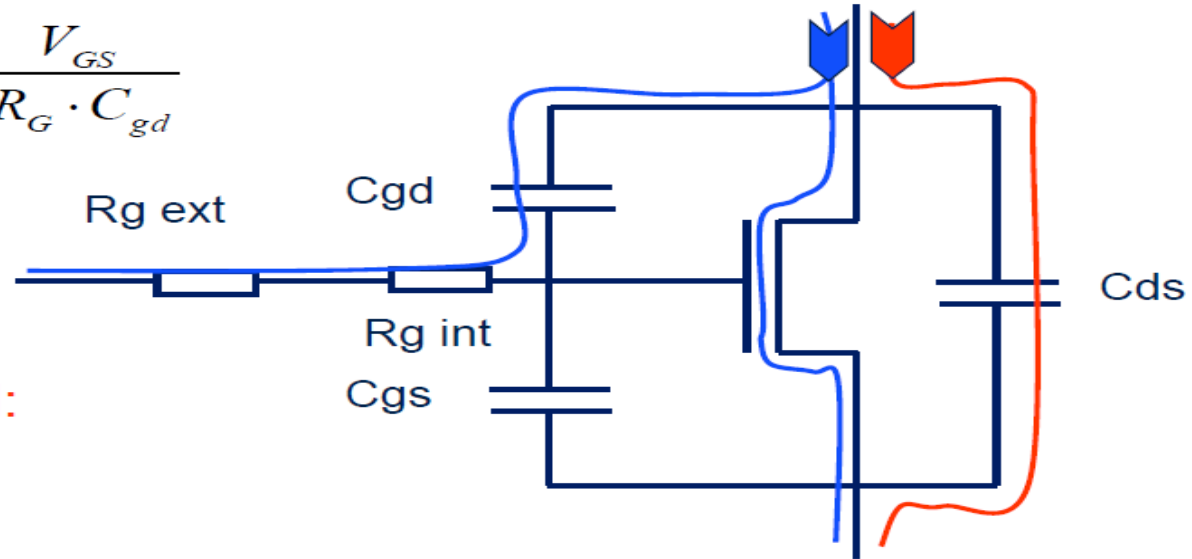
- External R_g
- External C_{gd}
- External C_{ds}
- Ferrite beads
- Transformers

Gate control:

$$dv/dt = \frac{I_G}{C_{gd}} = \frac{V_{GS}}{R_G \cdot C_{gd}}$$

Coss control:

$$dv/dt = \frac{I_l}{C_{oss}}$$



The well-known way to control the switching speed and therefore the EMI behavior is a variation of the external gate resistance. If the resistance will be increased, the time constant determined by this resistance and the capacitance of the MOSFET will be increased as well. The switching transient will be slowed down and thereby the electrical noise becomes lower

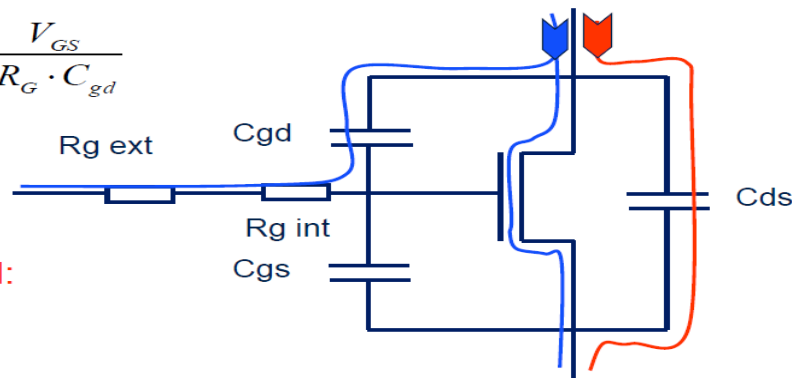
Increasing R_g reduce dv/dt

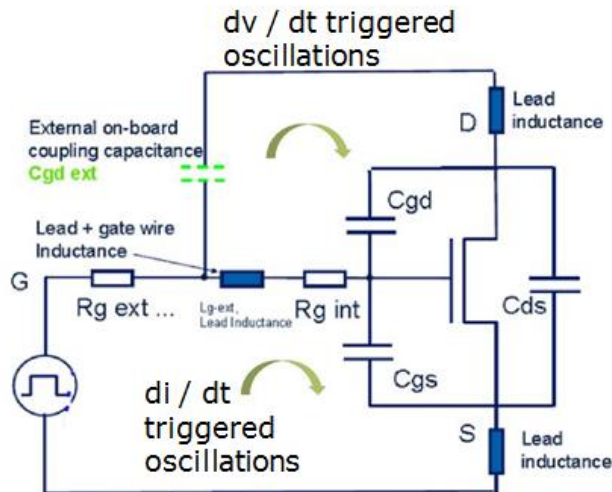
Gate control:

$$dv/dt = \frac{I_G}{C_{gd}} = \frac{V_{GS}}{R_G \cdot C_{gd}}$$

Coss control:

$$dv/dt = \frac{I_l}{C_{oss}}$$

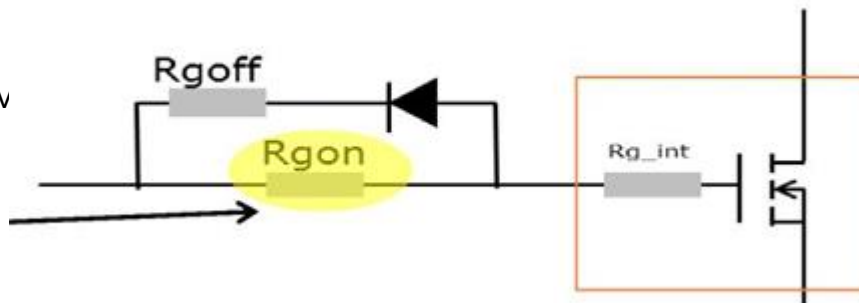




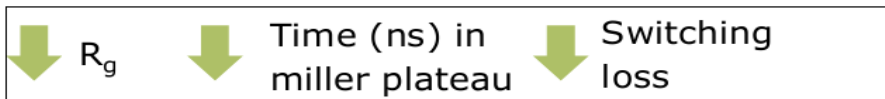
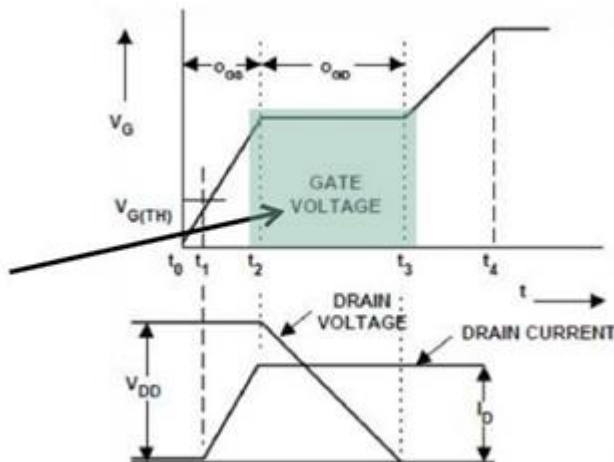
Integrated R_g suppresses oscillations due to dv/dt and di/dt internal to the device

Separating R_{gon} and R_{goff} helps

- > Adjust MOSFET turn-on and turn-off behavior individually
- > Turn-off resistor impacts efficiency
- Turn-on resistor impacts EMI

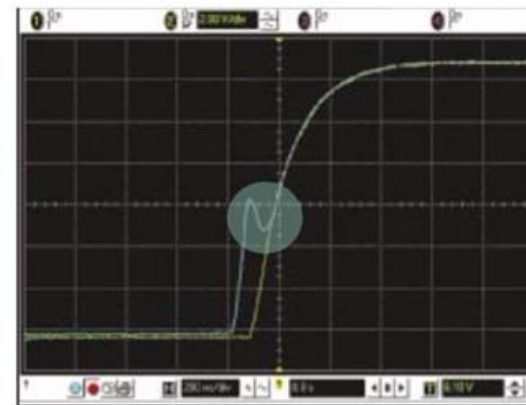


Miller plateau
in hard
switched
power supply



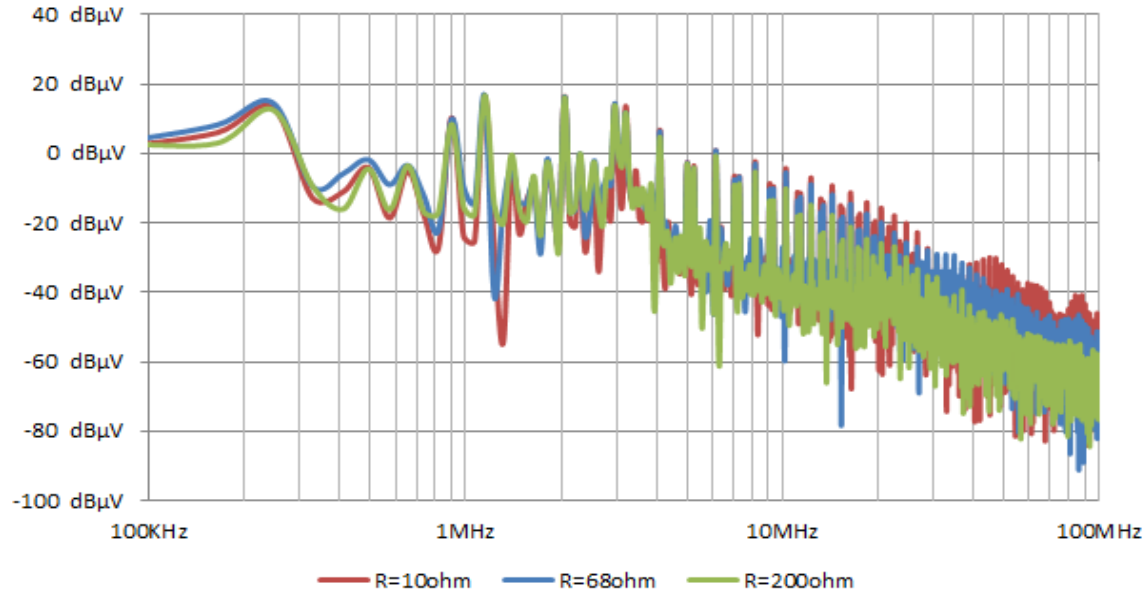
Time in miller plateau: $t = (R_g * C_{gd} * V_{ds}) / (V_{plateau} - V_{gsth})$

Power loss in miller plateau = $P_{av} * t = 0.5 * V * I_d * t$

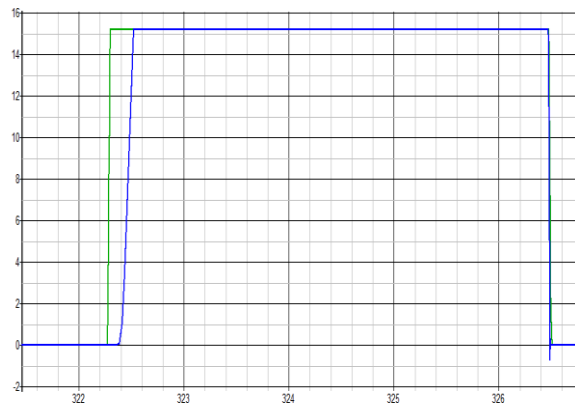
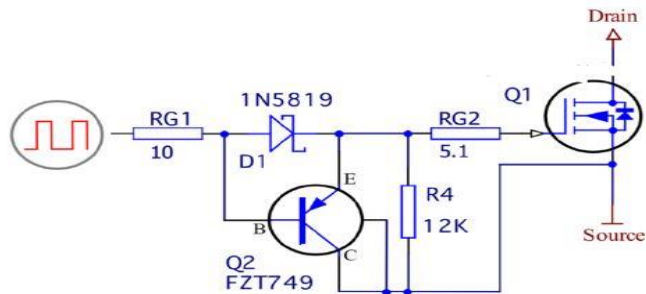


A quasi resonant (QR) flyback power supply has no miller plateau, so R_{gon} value has less impact on efficiency

This leads to **lower efficiency** and **higher temperature rise** on the CoolMOS™

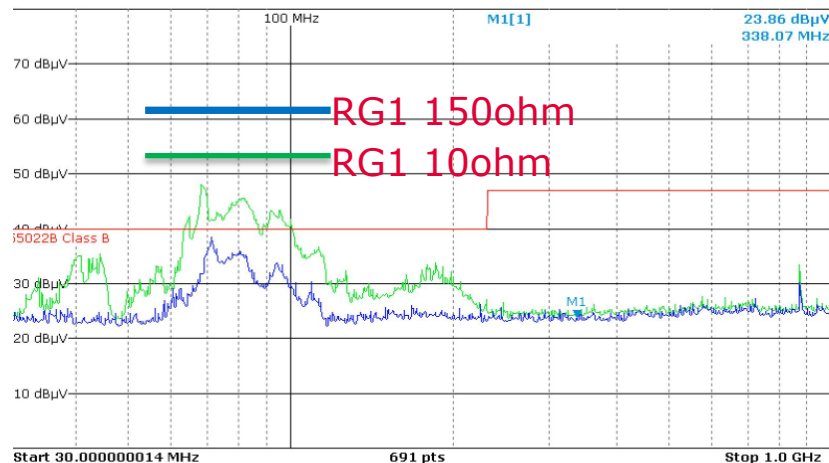


The noise emission can be also controlled in this way in high frequency range



Simulated gate voltage showing reduced
slew rate with higher R_g

Increasing external R_g ,
improves EMI by approx.
5 dBuV in less than 100 Mhz
frequency scan range



Simulated radiated emission scan

1

Introduction

2

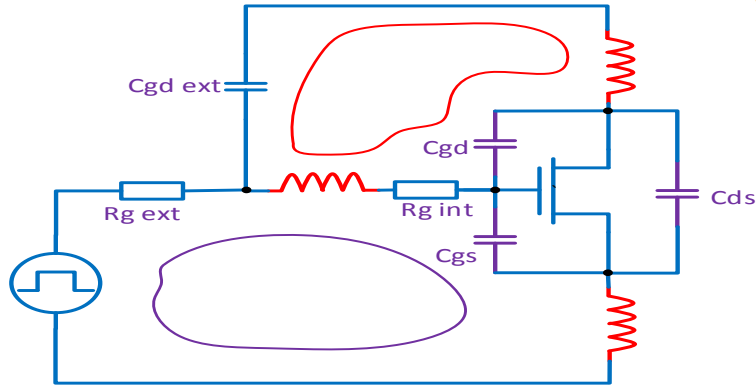
Methods to improve CoolMOS™ EMI behaviour

- External R_g
- External C_{gd}
- External C_{ds}
- Ferrite beads
- Transformers

Slowing the switching action of CoolMOSTM: Using external Cgd

Second method to control the switching speed and therefore the EMI behavior is addition of the external gate to drain capacitance. If the capacitance will be increased, the time constant determined by this resistance and the capacitance of the MOSFET will be increased as well. The switching transient will be slowed down and thereby the electrical noise becomes lower.

Increasing Cgd reduces dv/dt

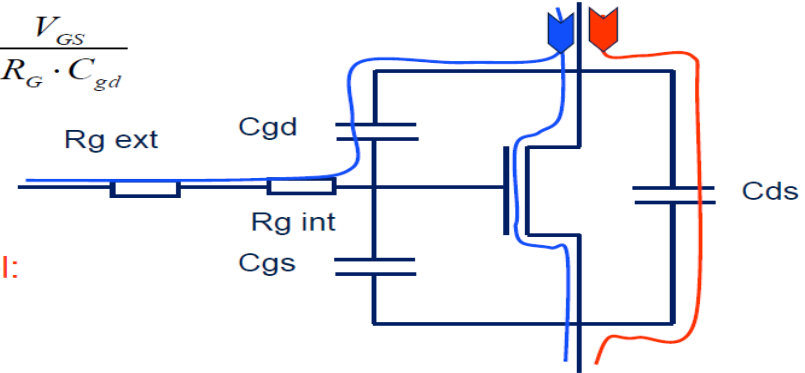


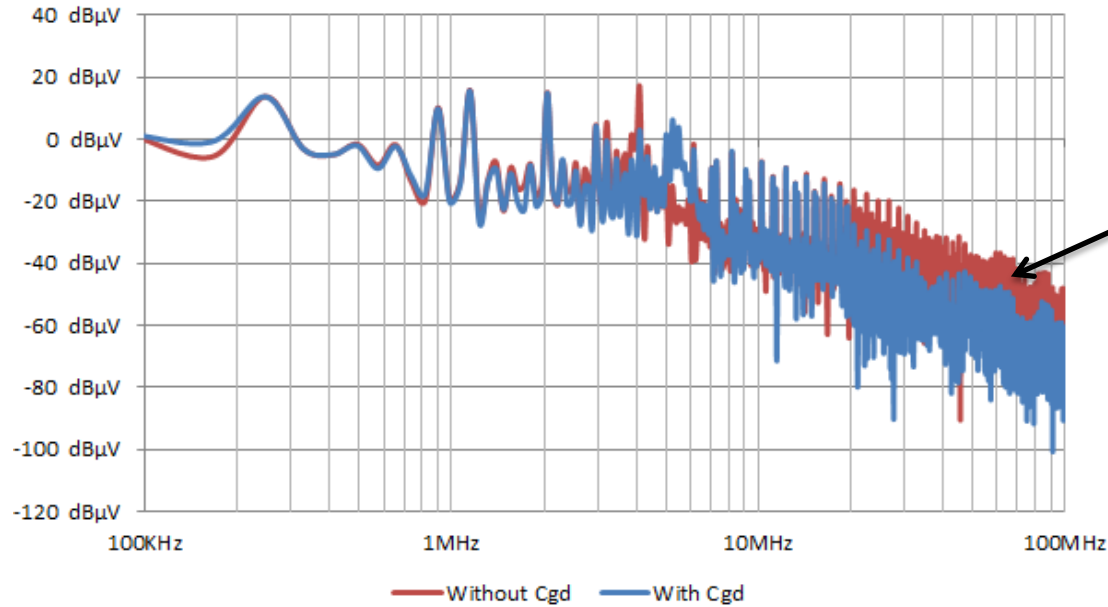
Gate control:

$$dv/dt = \frac{I_G}{C_{gd}} = \frac{V_{GS}}{R_G \cdot C_{gd}}$$

Coss control:

$$dv/dt = \frac{I_l}{C_{oss}}$$



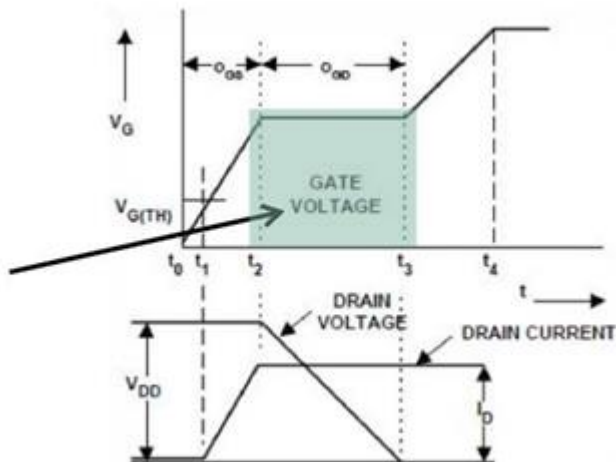


EMI reduced by
10 dBμV in high
scan frequency
range

Simulated EMI signature

Cgd limits to reduce EMI

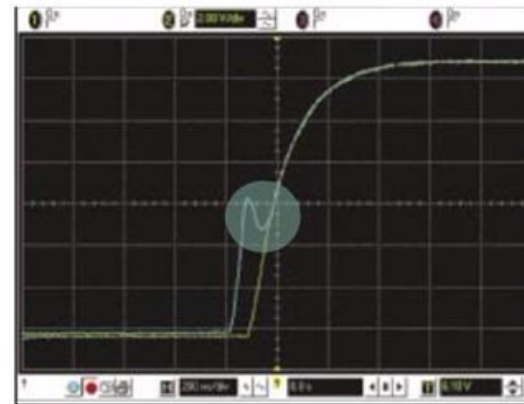
Miller plateau
in hard
switched
power supply



↑ C_{gd} ↑ Time (ns) in miller plateau ↑ Switching loss

Time in miller plateau: $t = (R_g * C_{gd} * V_{ds}) / (V_{plateau} - V_{gsth})$

Power loss in miller plateau = $P_{av} * t = 0.5 * V * I_D * t$



A quasi resonant (QR) flyback power supply has no miller plateau, so C_{gd} value has less impact on efficiency

This leads to **lower efficiency** and **higher temperature rise** on the CoolMOS™

1

Introduction

2

Methods to improve CoolMOS™ EMI behaviour

- External R_g
- External C_{gd}
- External C_{ds}
- Ferrite beads
- Transformers

Slowing the switching action of CoolMOS™:

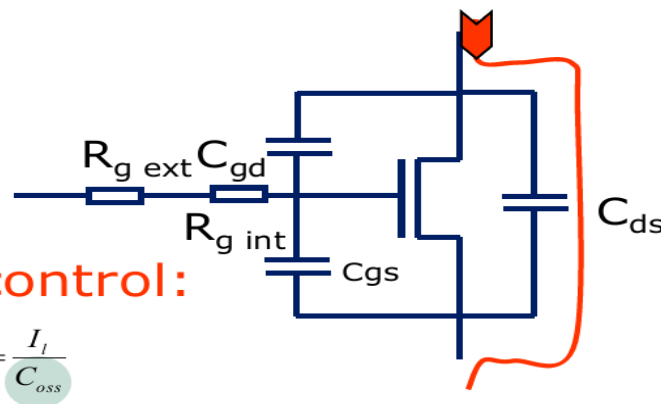
Using external Cds

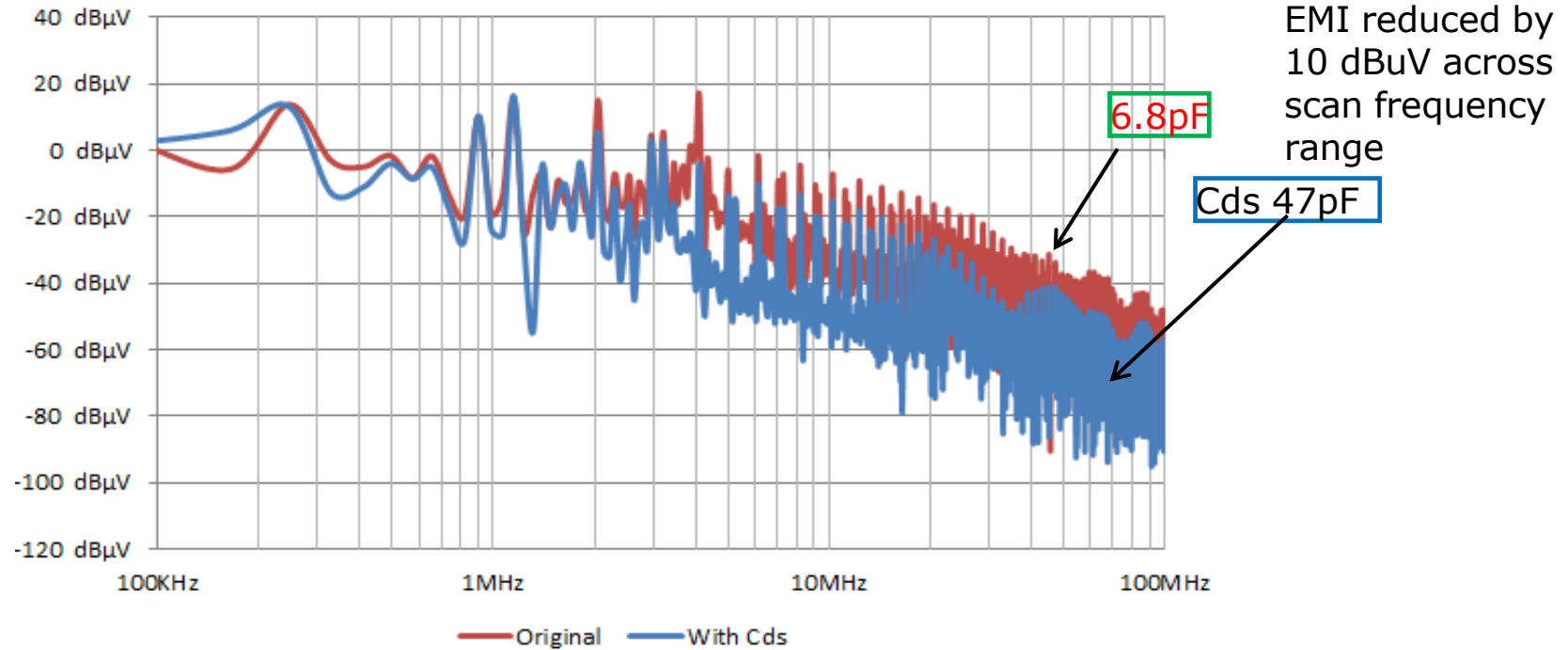
The third way to control the switching speed and therefore the EMI behavior is increasing the output capacitance of the MOSFET. If the capacitance will be increased in a Coss dependent switching like in the QR flyback, the switching transient will be slowed down and thereby the electrical noise becomes lower.

Increasing C_{ds} / C_{oss} reduces dv/dt

C_{oss} control:

$$dv/dt = \frac{I_l}{C_{oss}}$$





Simulated EMI signature

1

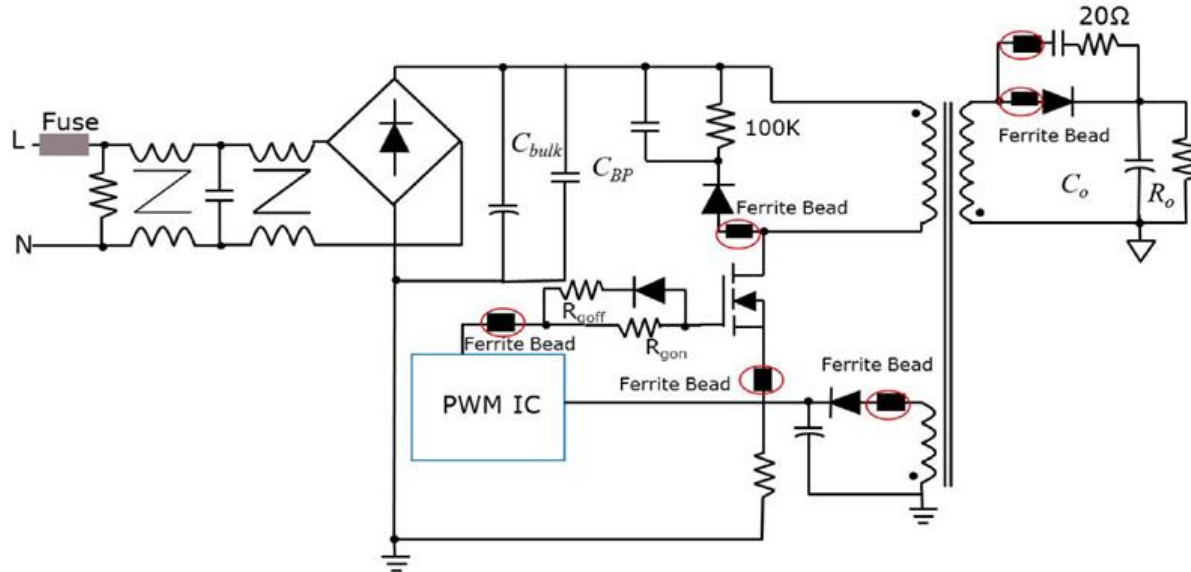
Introduction

2

Methods to improve CoolMOS™ EMI behaviour

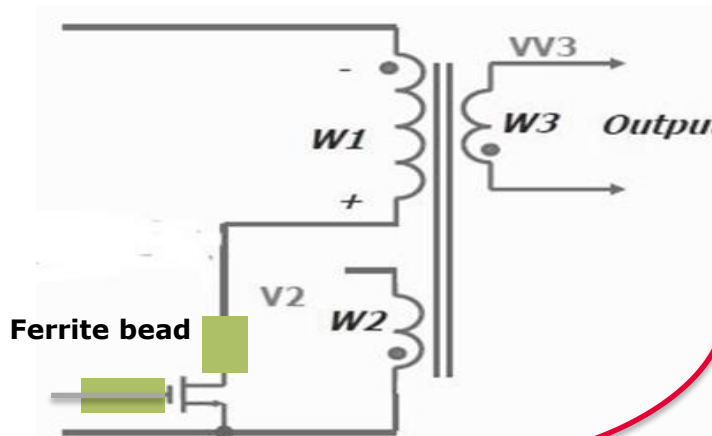
- External R_g
- External C_{gd}
- External C_{ds}
- Ferrite beads
- Transformers

$di/dt = V / L$, where V is the oscillation (noise) voltage and L is the stray inductance

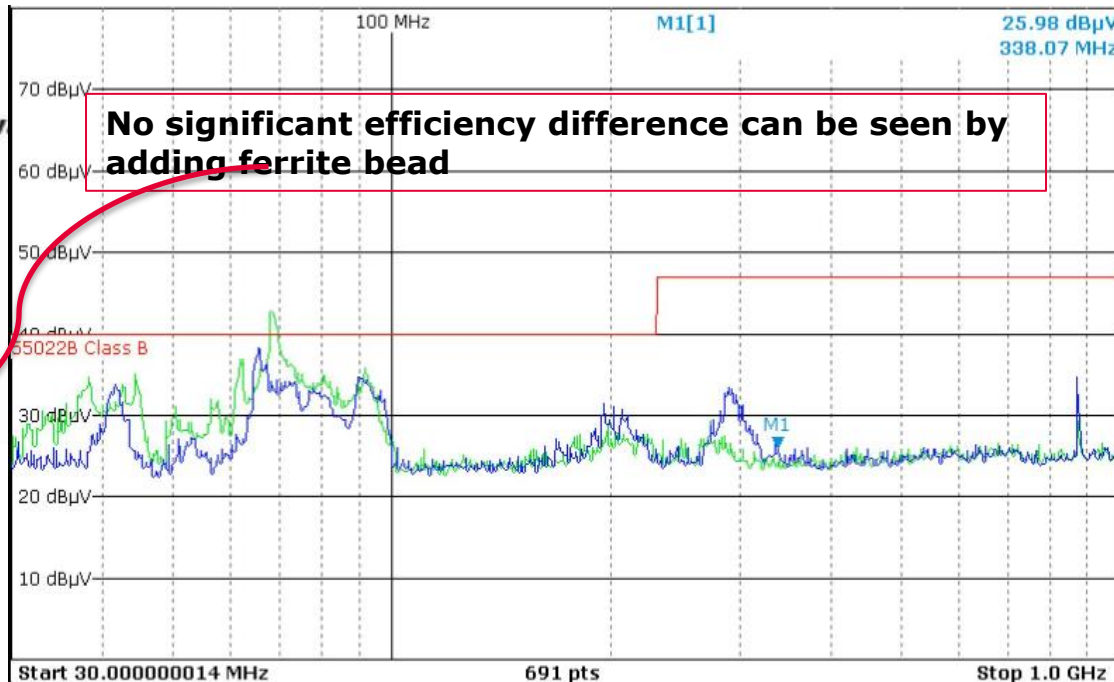


Use ferrite bead to reduce FET di/dt

Use of Ferrite bead to Suppression EMI(15W)



with Ferrite bead			without Ferrite bead		
V in	I out	Eff	V in	I out	Eff
90.01	0.4981	80.831	90.01	0.4981	80.841
90	0.8749	83.61971	90	0.8749	83.60971
90.01	1.2504	84.63238	90.01	1.2504	84.61238
90.01	1.6251	85.679	90.01	1.6251	85.66
90.01	1.9998	86.25454	90.01	1.9998	86.252
264.16	0.4983	86.8961	264.16	0.4983	86.8961
264.15	0.8748	87.8801	264.15	0.8748	87.8801
264.16	1.2502	88.01185	264.16	1.2502	88.02
264.16	1.625	87.62	264.16	1.625	87.6
264.15	1.9997	87.01646	264.15	1.9997	87.1



— Without Ferrite bead
— With Ferrite bead

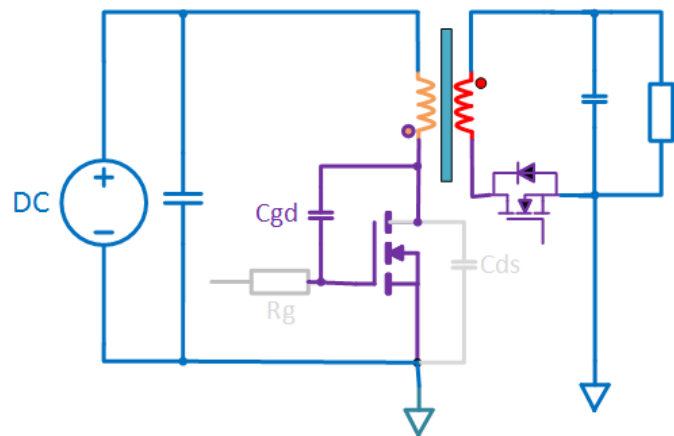
1

Introduction

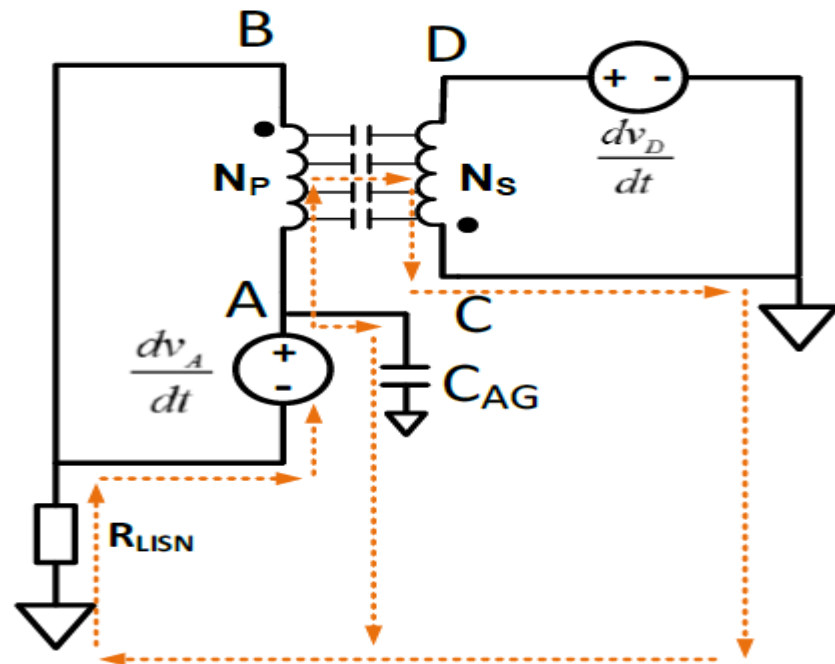
2

Methods to improve CoolMOS™ EMI behaviour

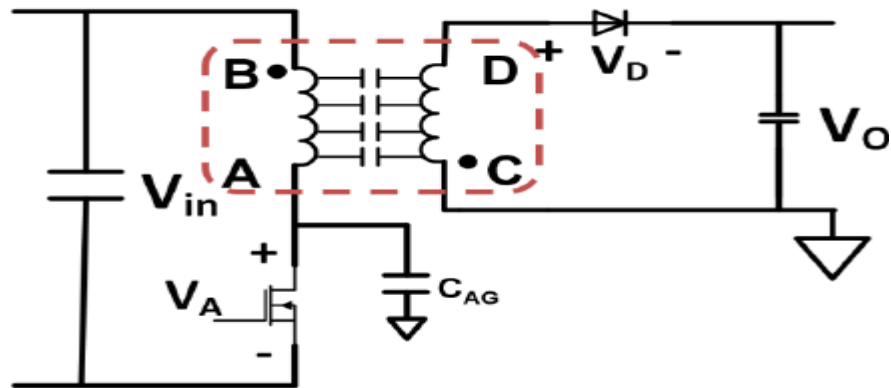
- External R_g
- External C_{gd}
- External C_{ds}
- Ferrite beads
- Transformers



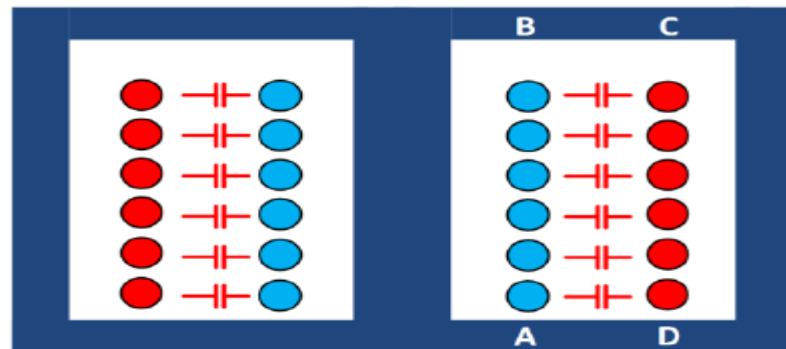
反激变换器拓扑



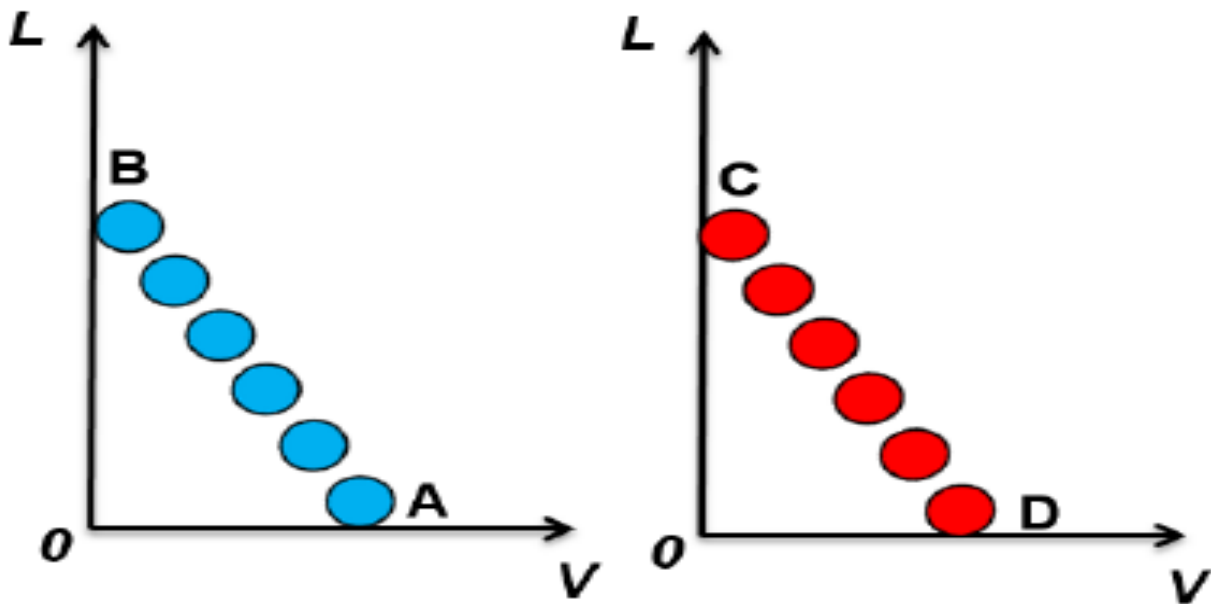
反激变换器的共模噪声传播路径



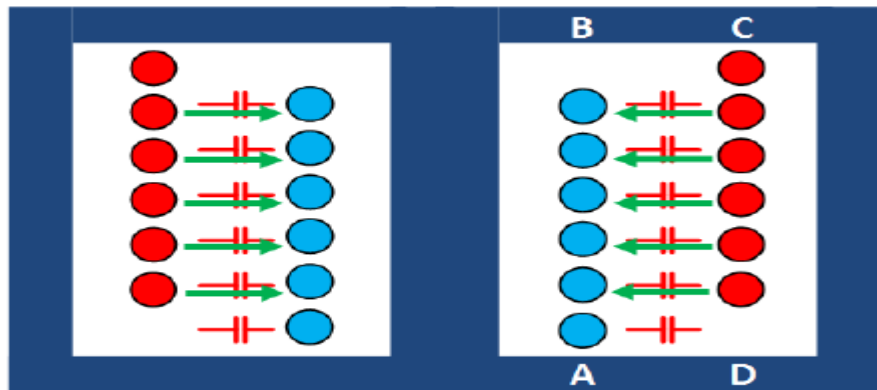
反激电路拓扑



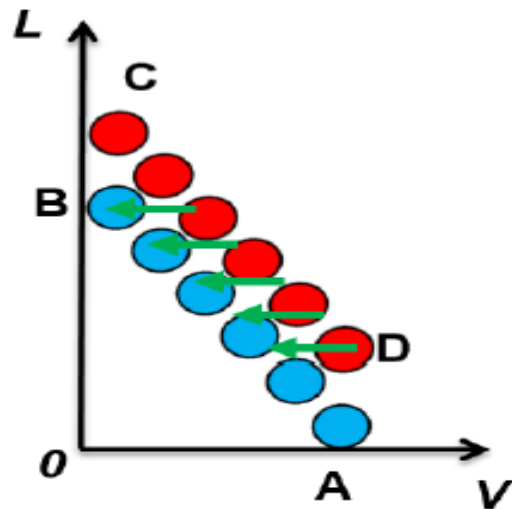
1: 1变压器结构图



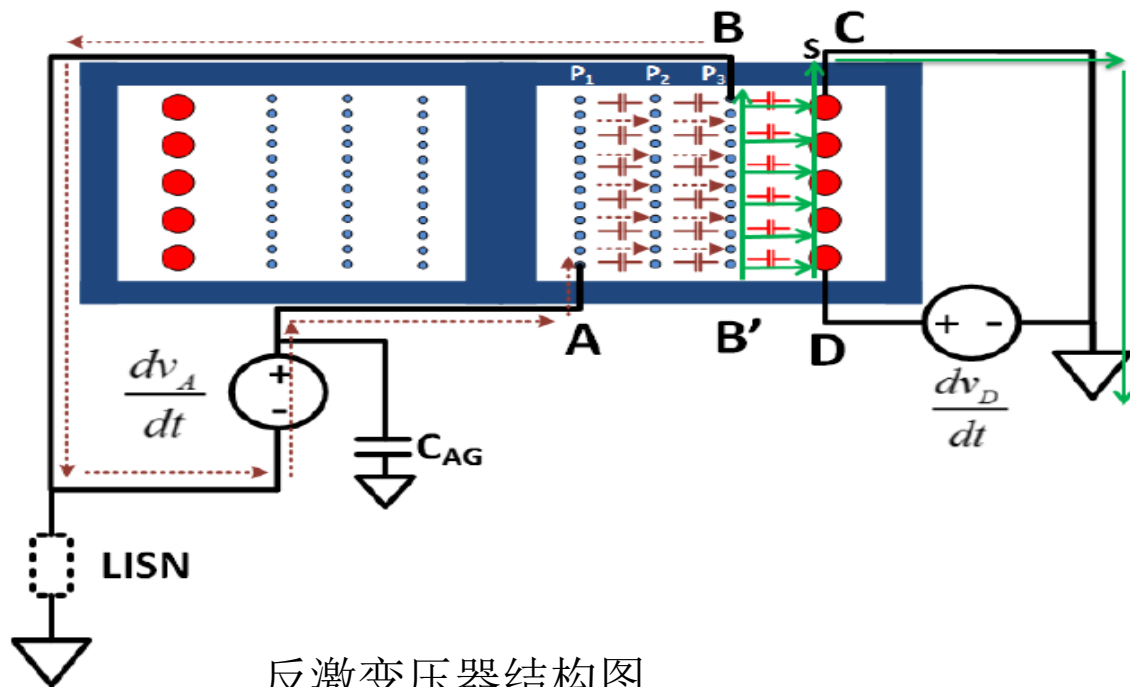
初级绕组和次级绕组的电压分布

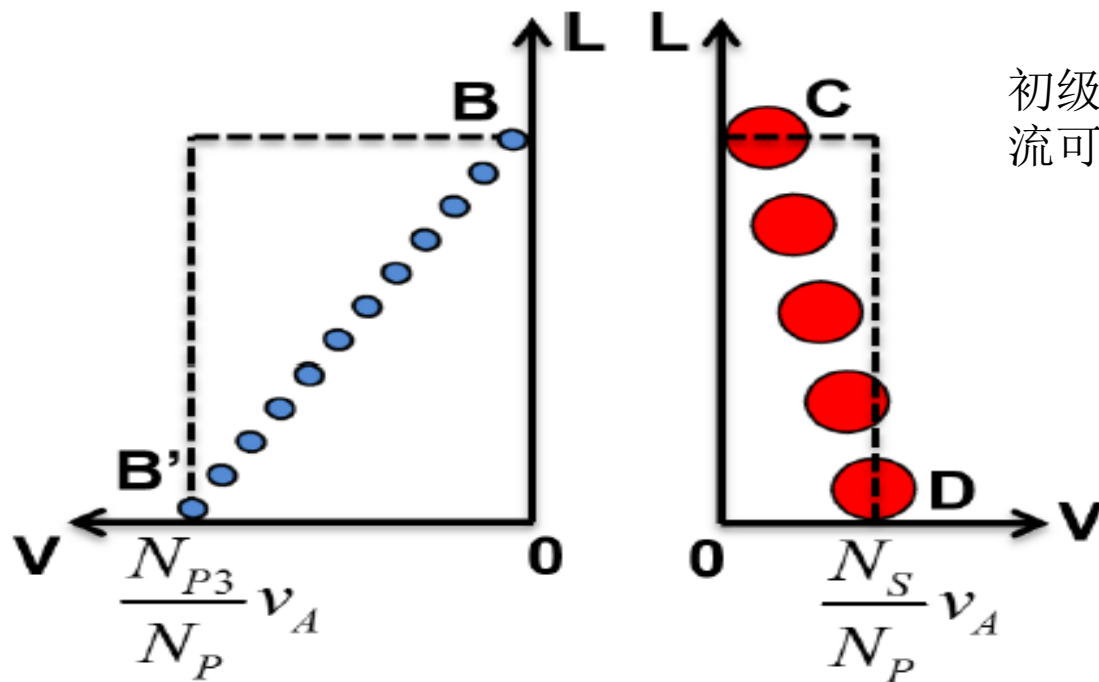


当线组不重合时



初级绕组和次级绕组的电压分布

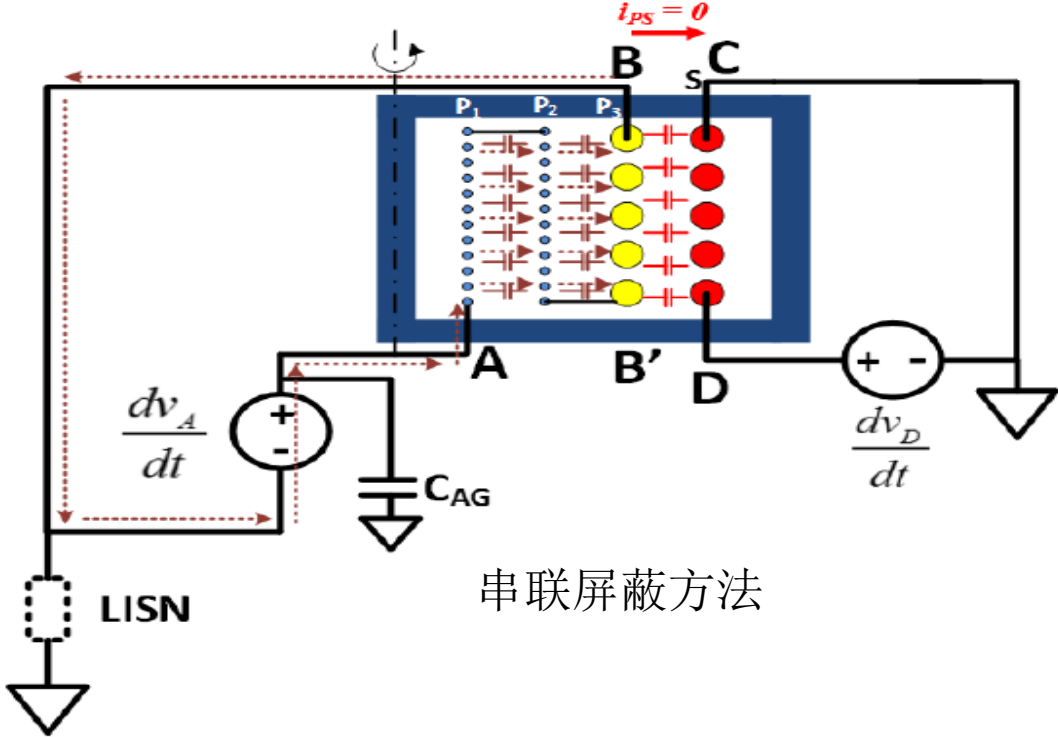




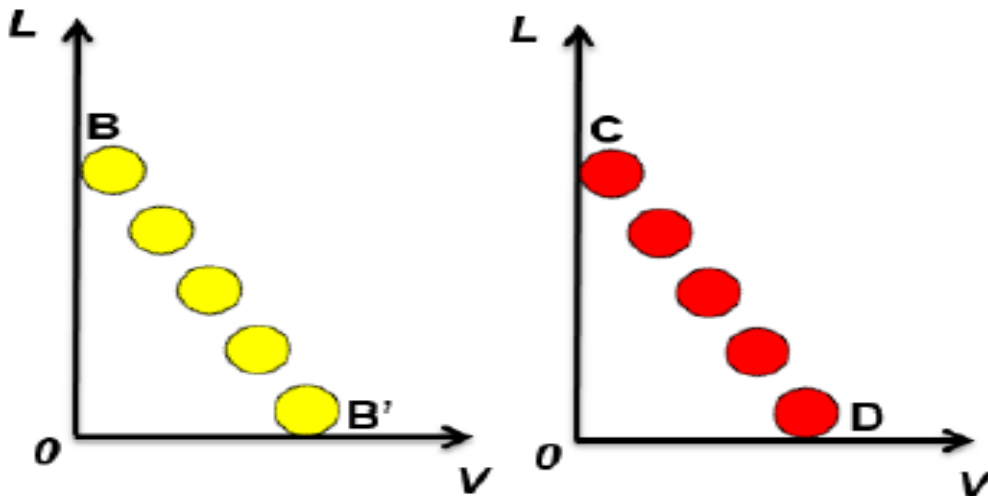
初级线组到次级绕组的总位移电流可以计算出：

$$i = C_{PS} \frac{d}{dt} \frac{v_A}{2N_P} (N_{P3} - N_S)$$

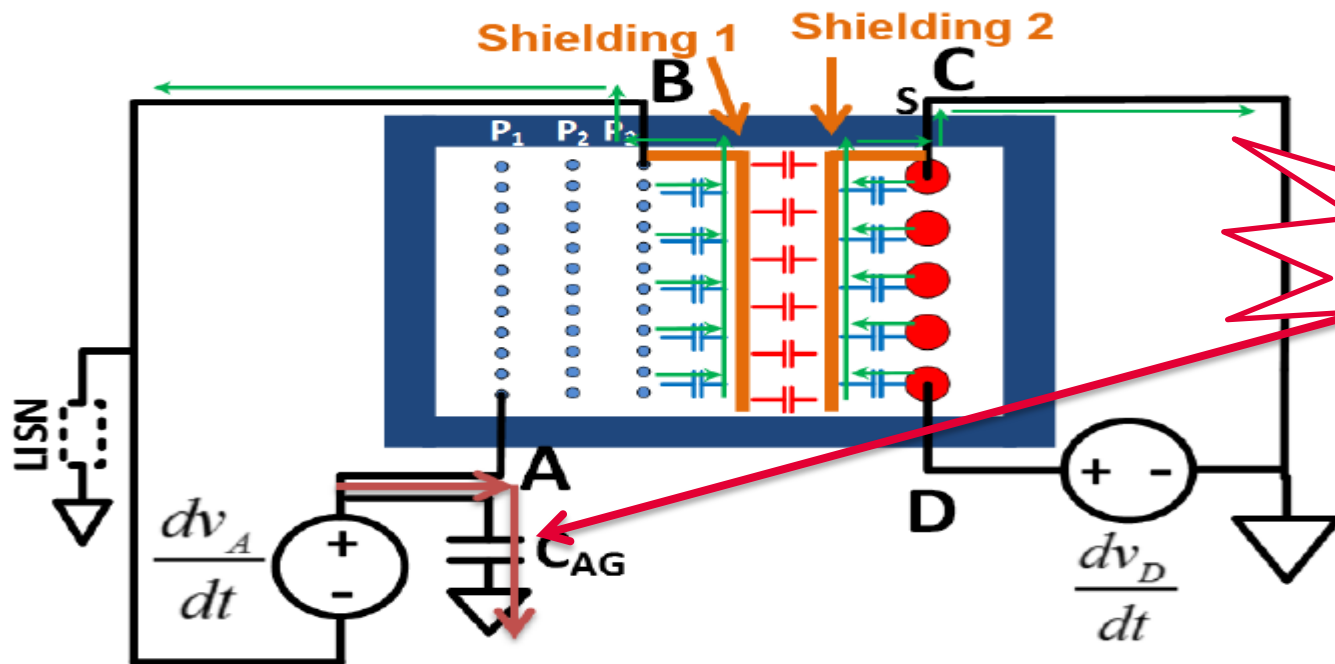
初级P3绕组和次级绕组的电压分布



串联屏蔽方法

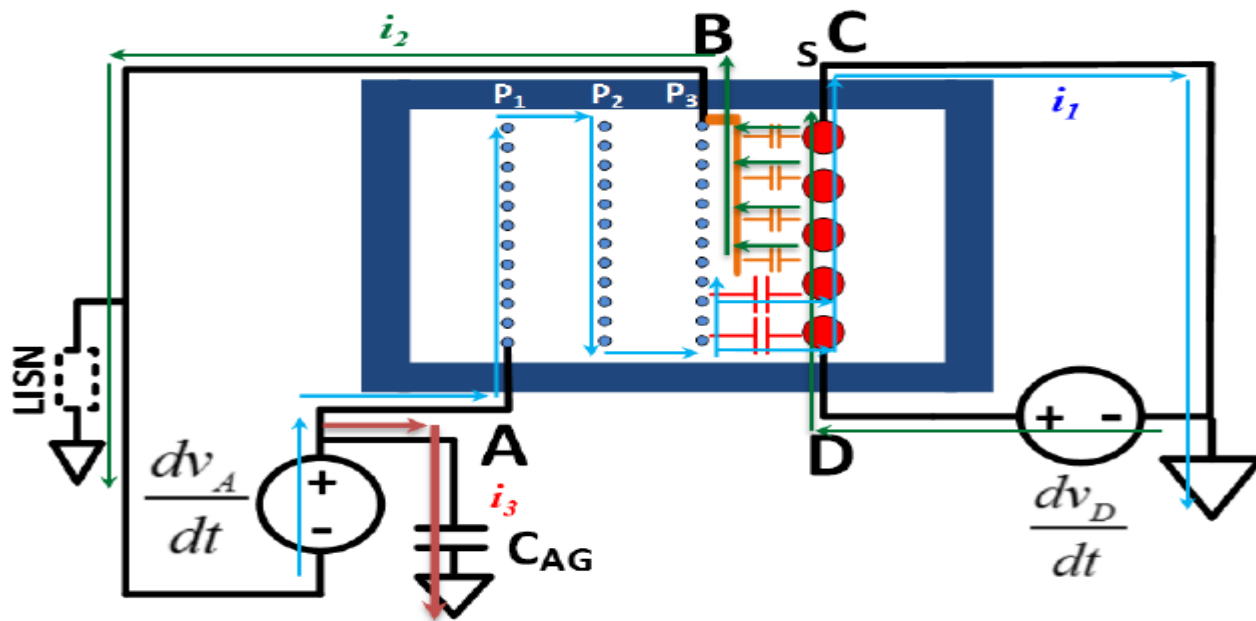


初级P3绕组和次级绕组的电压分布

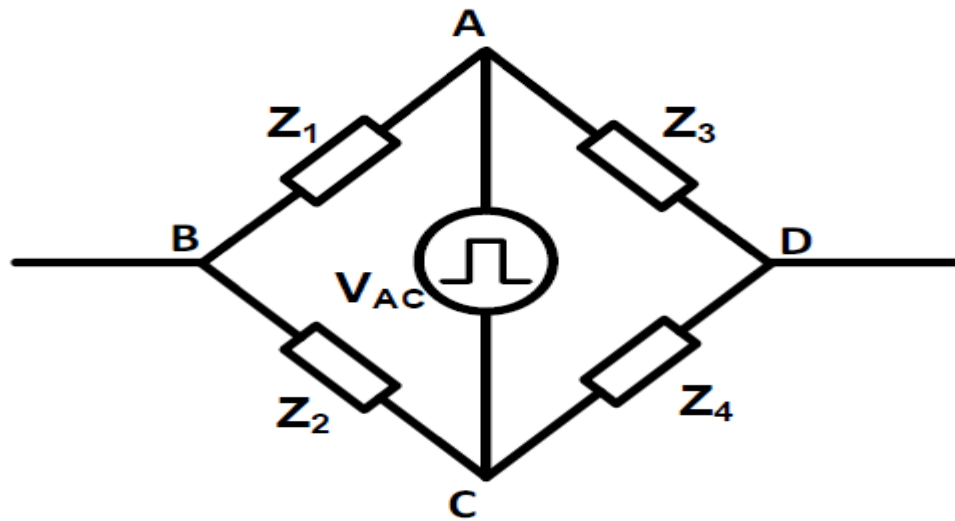


不能减小该路径
的共模噪声

两层屏蔽方法



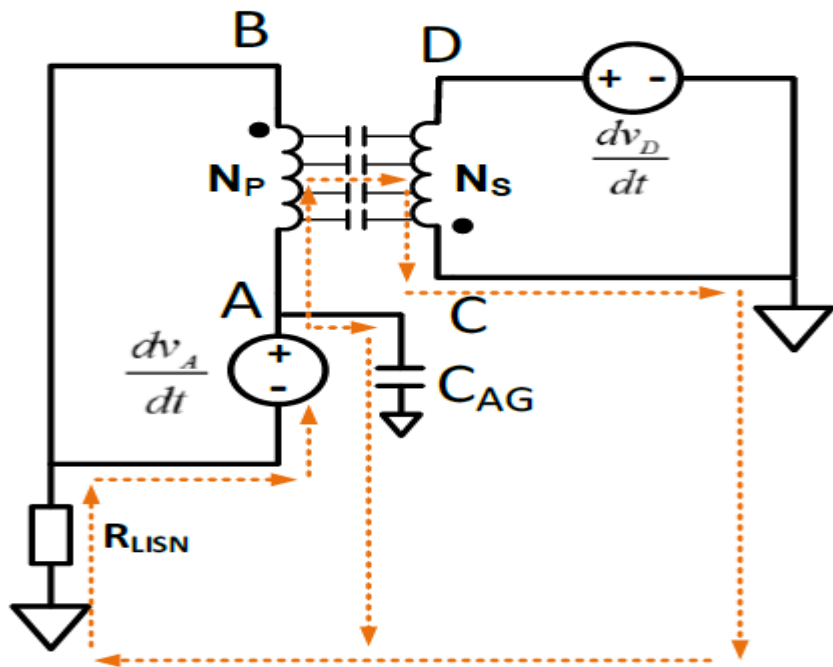
$$i_1 + i_2 + i_3 = 0$$



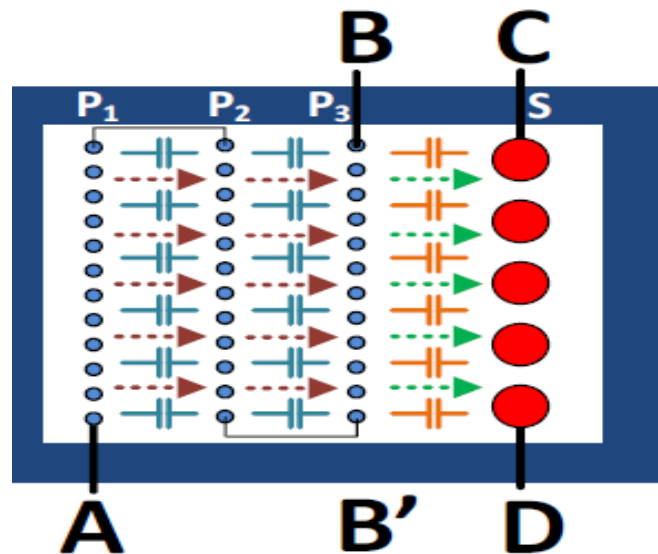
当 $Z_1/Z_2 = Z_3/Z_4$ 电桥平衡，B点与D点电压一样因此没有电流流过。

惠斯登电桥结构

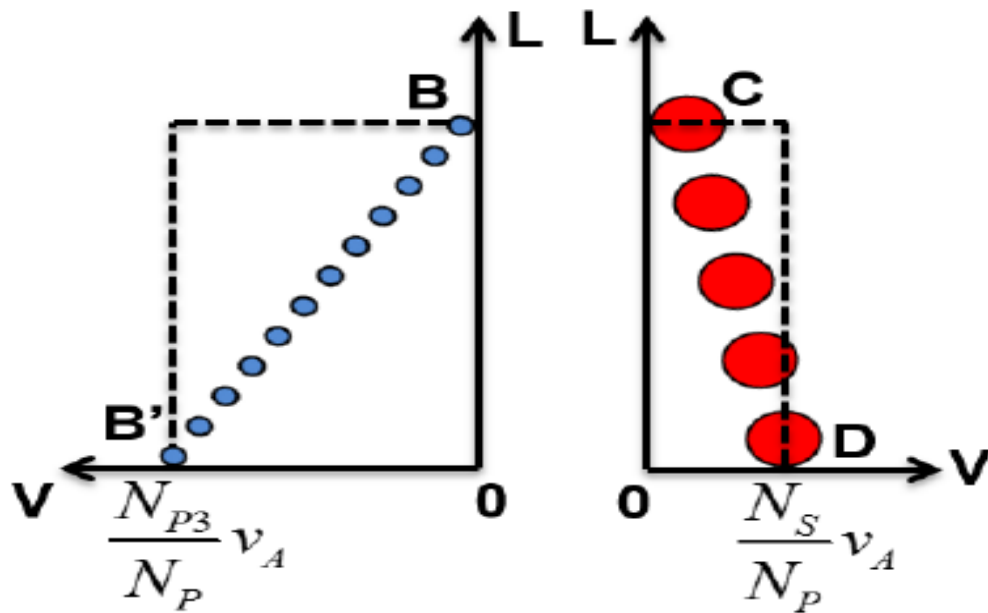
$$\frac{Z_1}{Z_2} = \frac{Z_3}{Z_4}$$



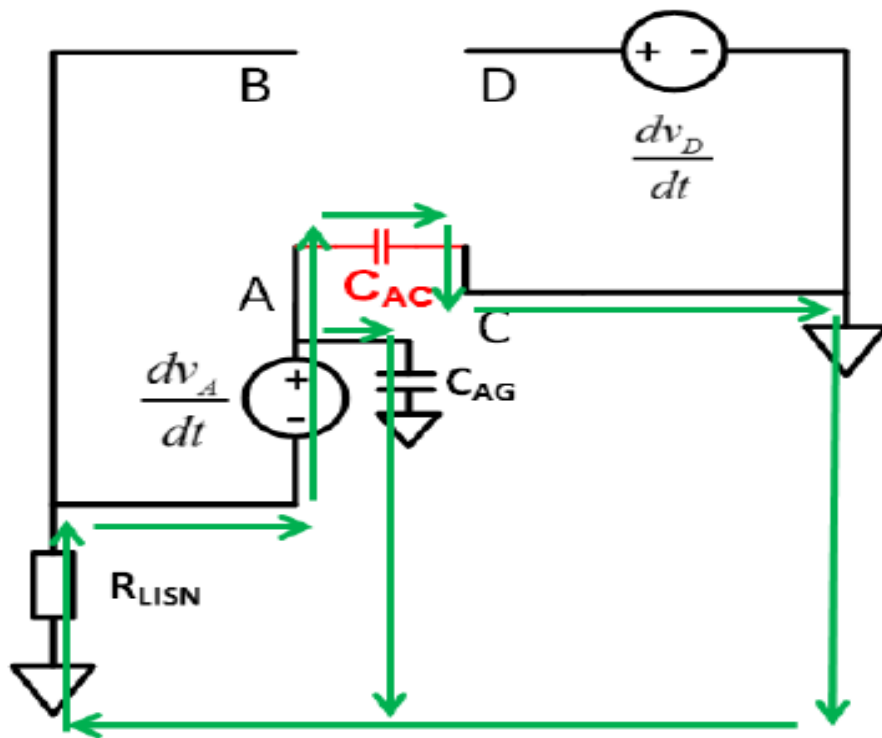
使用电压源取代MOSFET



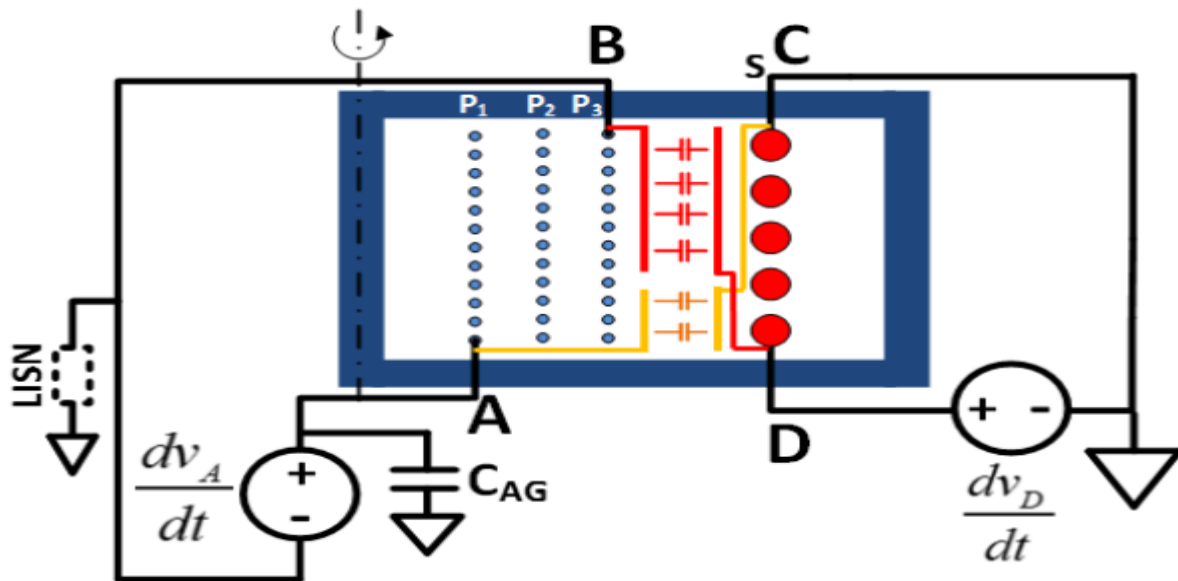
变压器结构

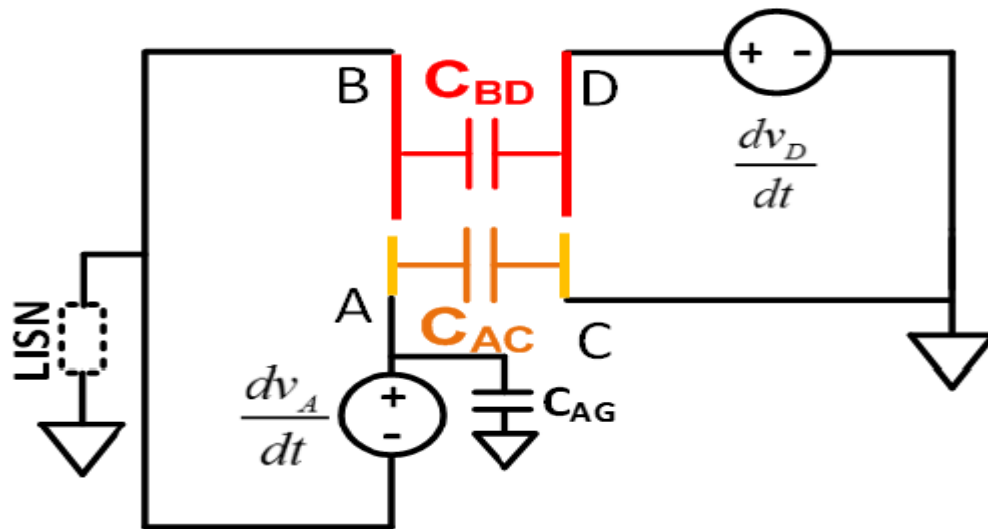


$$i = C_{PS} \frac{d}{dt} \frac{v_A}{2N_P} (N_{P3} - N_S)$$

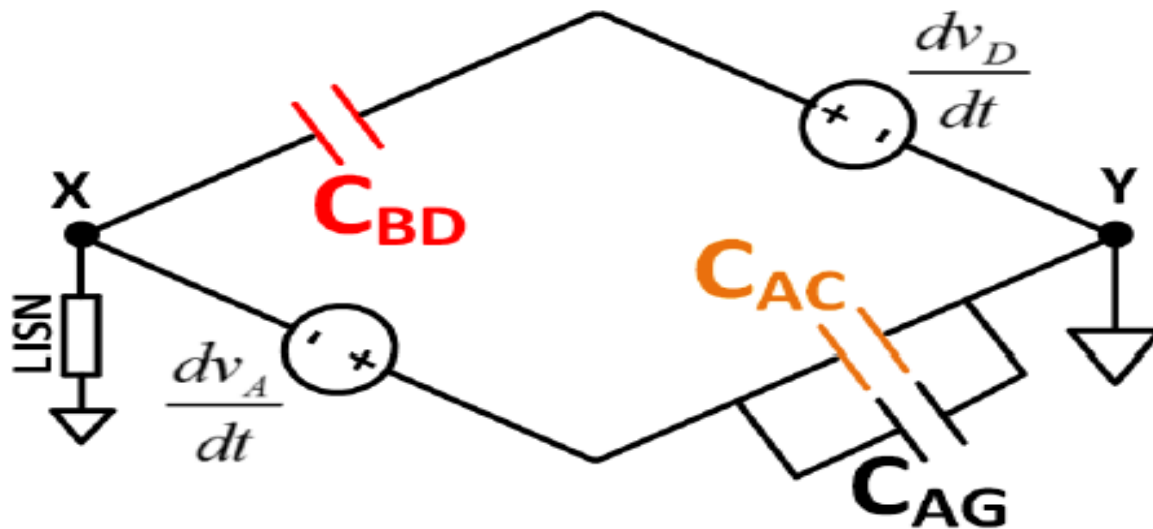


反激变换器的共模噪声



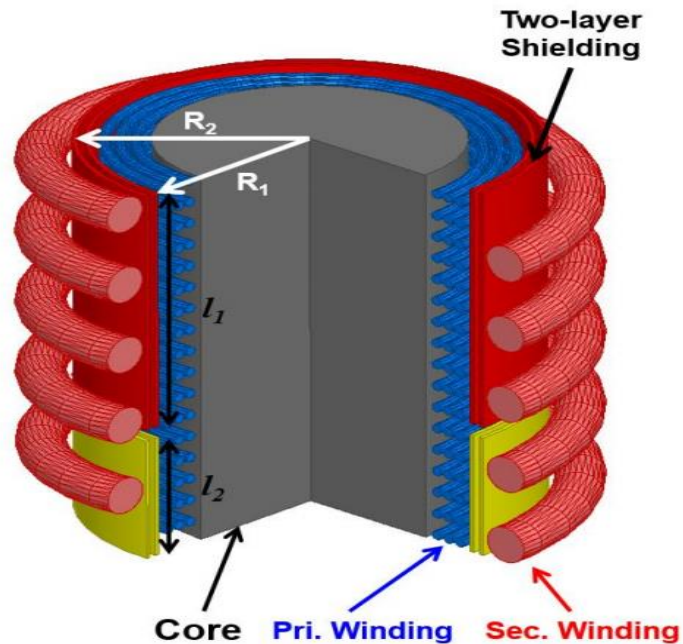


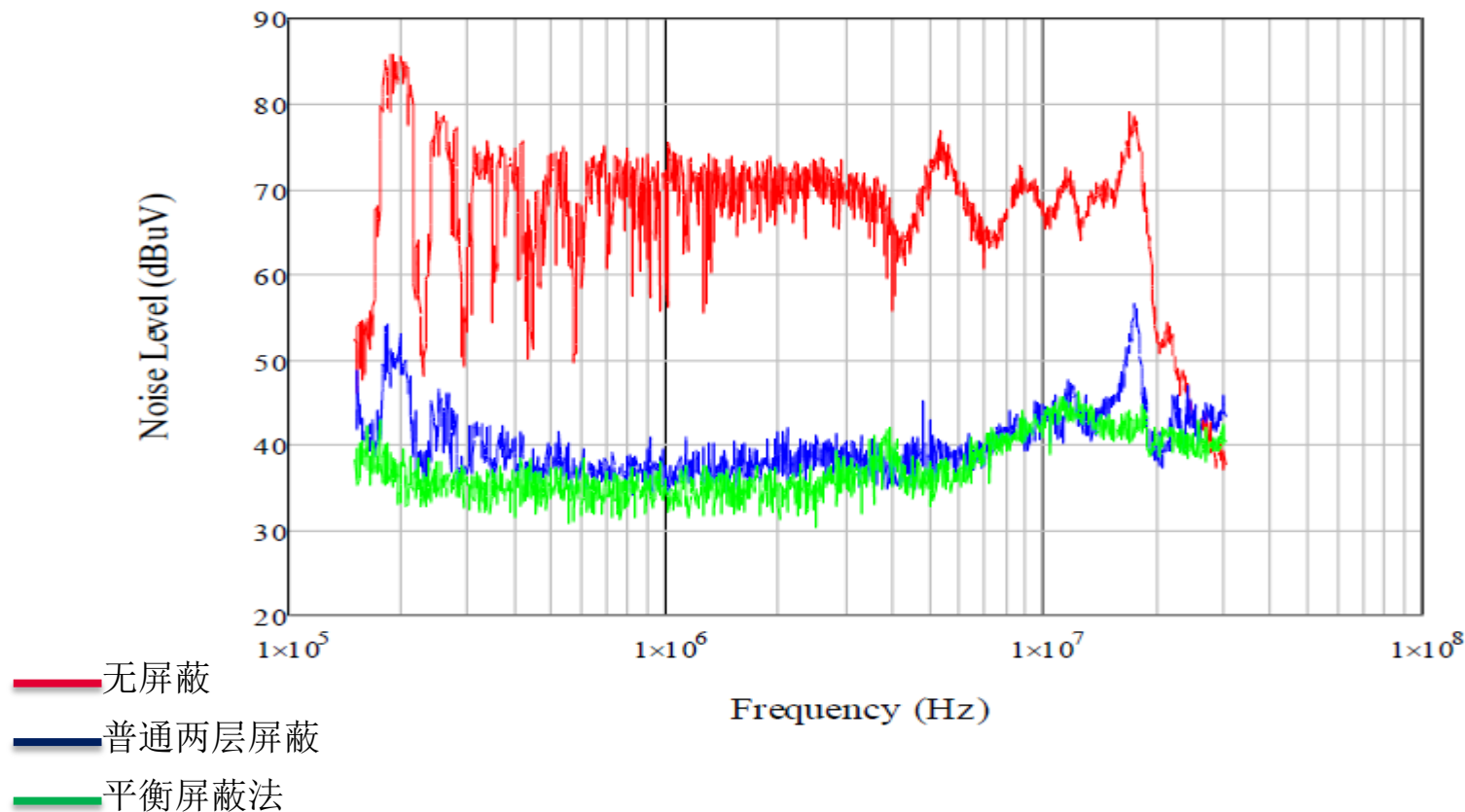
使用双屏蔽平衡技巧的反激变换器共模噪声模型

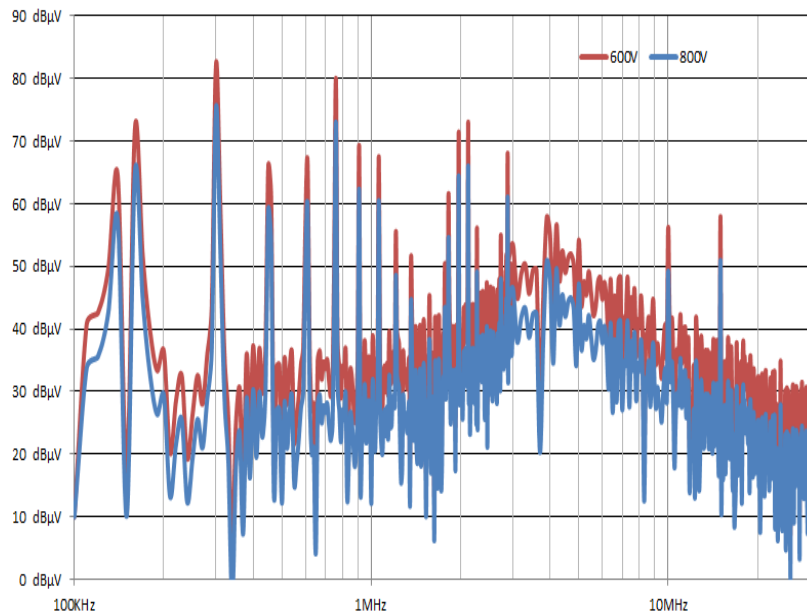


桥式电路的CM模型

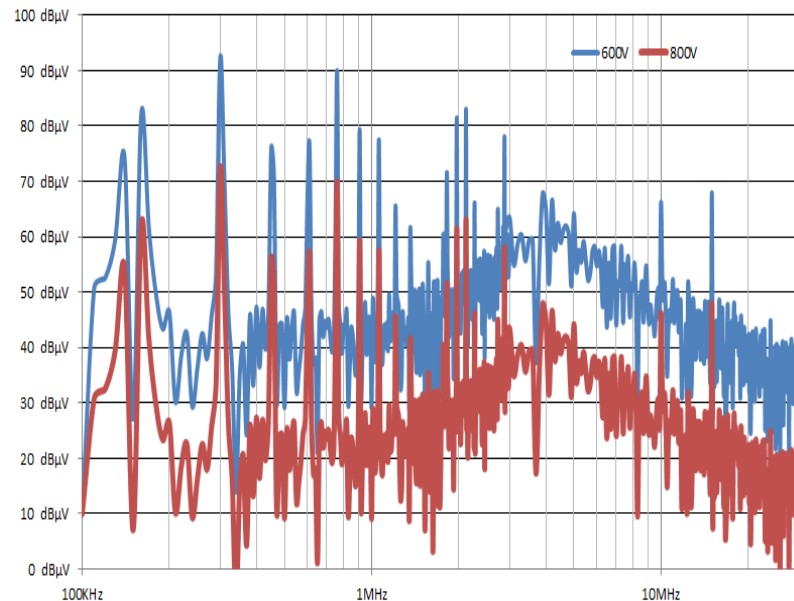
$$\frac{dv_A/dt}{dv_D/dt} = \frac{C_{BD}}{C_{AC} + C_{AG}}$$







图A 漏源极电压的频谱比较



图B 漏源极电流的频谱比较



Part of your life. Part of tomorrow.

